CLAIMS:

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1. A resist composition comprising at least one basic compound having an imidazole skeleton and a polar functional group, represented by the general formula (1):

$$\begin{array}{c}
R^2 \\
N - R^2 \\
R^3 R^4
\end{array}$$
(1)

wherein R¹ is a straight, branched or cyclic alkyl group of 2 to 20 carbon atoms bearing at least one polar functional group selected from among hydroxyl, carbonyl, ester, ether, sulfide, carbonate, cyano and acetal groups; R², R³ and R⁴ are each independently a hydrogen atom, a straight, branched or cyclic alkyl group of 1 to 10 carbon atoms, an aryl group of 6 to 10 carbon atoms, or an aralkyl group of 7 to 10 carbon atoms.

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2. A resist composition comprising at least one basic compound represented by the general formulae (2) to (6):

wherein R^2 , R^3 and R^4 are each independently a hydrogen atom, a straight, branched or cyclic alkyl group of 1 to 10 carbon atoms, an aryl group of 6 to 10 carbon atoms, or an aralkyl group of 7 to 10 carbon atoms;

 R^5 , R^7 , R^9 and R^{13} are each independently a straight, branched or cyclic alkylene group of 1 to 10 carbon atoms;

R⁶ and R⁸ are each independently a hydrogen atom or an alkyl group of 1 to 15 carbon atoms which may contain at least one group selected from among hydroxyl, carbonyl, ester, ether, sulfide, carbonate, cyano and acetal groups;

R¹⁰ is an alkyl group of 1 to 15 carbon atoms which may contain at least one group selected from among hydroxyl, carbonyl, ester, ether, sulfide, carbonate, cyano and acetal groups;

R¹¹ is a (n+1)-valent, straight, branched or cyclic hydrocarbon group of 2 to 10 carbon atoms;

R¹² is each independently a hydrogen atom or an alkyl group of 1 to 15 carbon atoms which may contain at least one group selected from among hydroxyl, carbonyl, ester, ether, sulfide, carbonate, cyano and acetal groups, or two of R¹² may bond together to form a ring; and

n is equal to 2, 3, 4 or 5.

- 3. A positive-working resist composition comprising:
 - (A) the basic compound of claim 1;
 - (B) an organic solvent;

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- (C) a base resin having an acid labile group-protected acidic functional group which is alkali-insoluble or substantially alkali-insoluble, but becomes alkali-soluble when the acid labile group is eliminated; and
 - (D) a photoacid generator.
- 4. The positive resist composition of claim 3 which further comprises (E) a dissolution inhibitor.

- 5. A negative-working resist composition comprising:
 - (A) the basic compound of claim 1;
 - (B) an organic solvent;
- (C') a base resin which is alkali-soluble, but becomes
 substantially alkali-insoluble when crosslinked with a
 crosslinking agent;
 - (D) a photoacid generator; and
 - (F) a crosslinking agent which induces crosslinkage under the action of an acid.

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- 6. A patterning process comprising the steps of:
- (1) applying the positive resist composition of claim3 onto a substrate;
- (2) heat treating the applied resist, then exposing
 the heat-treated resist through a photomask to high-energy
 radiation having a wavelength of at most 300 nm or an
 electron beam; and
 - (3) heat treating the exposed resist, then developing the resist with a liquid developer.

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- 7. A patterning process comprising the steps of:
- (1) applying the negative resist composition of claim5 onto a substrate;
- (2) heat treating the applied resist, then exposing the heat-treated resist through a photomask to high-energy radiation having a wavelength of at most 300 nm or an electron beam; and
 - (3) heat treating the exposed resist, then developing the resist with a liquid developer.

8. A basic compound represented by the general formula(2):

wherein R², R³ and R⁴ are each independently a hydrogen atom, a straight, branched or cyclic alkyl group of 1 to 10 carbon atoms, an aryl group of 6 to 10 carbon atoms, or an aralkyl group of 7 to 10 carbon atoms;

 ${\tt R}^{\tt 5}$ is a straight, branched or cyclic alkylene group of 1 to 10 carbon atoms; and

10 R⁶ is a hydrogen atom or an alkyl group of 1 to 15 carbon atoms which may contain at least one group selected from among hydroxyl, carbonyl, ester, ether, sulfide, carbonate, cyano and acetal groups.

9. A basic compound represented by the general formula (3):

wherein R^2 , R^3 and R^4 are each independently a hydrogen atom, a straight, branched or cyclic alkyl group of 1 to 10 carbon atoms, an aryl group of 6 to 10 carbon atoms, or an aralkyl group of 7 to 10 carbon atoms;

 R^7 is a straight, branched or cyclic alkylene group of 1 to 10 carbon atoms; and

 R^8 is a hydrogen atom or an alkyl group of 1 to 15 carbon atoms which may contain at least one group selected

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from among hydroxyl, carbonyl, ester, ether, sulfide, carbonate, cyano and acetal groups.

10. A basic compound represented by the general formula5 (4):

wherein R², R³ and R⁴ are each independently a hydrogen atom, a straight, branched or cyclic alkyl group of 1 to 10 carbon atoms, an aryl group of 6 to 10 carbon atoms, or an aralkyl group of 7 to 10 carbon atoms;

 ${\tt R}^{9}$ is a straight, branched or cyclic alkylene group of 1 to 10 carbon atoms; and

 R^{10} is an alkyl group of 1 to 15 carbon atoms which may contain at least one group selected from among hydroxyl, carbonyl, ester, ether, sulfide, carbonate, cyano and acetal groups.

11. A basic compound represented by the general formula (5):

$$\begin{array}{ccc}
R^2 \\
N & R^{11} \\
R^3 & R^4
\end{array}$$
(5)

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wherein R^2 , R^3 and R^4 are each independently a hydrogen atom, a straight, branched or cyclic alkyl group of 1 to 10 carbon atoms, an aryl group of 6 to 10 carbon atoms, or an aralkyl group of 7 to 10 carbon atoms;

 R^{11} is a (n+1)-valent, straight, branched or cyclic hydrocarbon group of 2 to 10 carbon atoms;

 R^{12} is each independently a hydrogen atom or an alkyl group of 1 to 15 carbon atoms which may contain at least one group selected from among hydroxyl, carbonyl, ester, ether, sulfide, carbonate, cyano and acetal groups, or two of R^{12} may bond together to form a ring; and

n is equal to 2, 3, 4 or 5.

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10 12. A basic compound represented by the general formula (6):

$$\begin{array}{cccc}
R^2 & & & \\
N & & & & \\
N & & & & \\
R^3 & & & & \\
R^4 & & & & \\
\end{array}$$
(6)

wherein R^2 , R^3 and R^4 are each independently a hydrogen atom, a straight, branched or cyclic alkyl group of 1 to 10 carbon atoms, an aryl group of 6 to 10 carbon atoms, or an aralkyl group of 7 to 10 carbon atoms; and

 ${\ensuremath{\mathsf{R}}}^{13}$ is a straight, branched or cyclic alkylene group of 1 to 10 carbon atoms.